

**Carbon Tetrafluoride (CF<sub>4</sub>)**

Product Name	Carbon Tetrafluoride
Synonyms	Tetrafluoromethane
Molecular Formula	CF <sub>4</sub>
CAS No.	75-73-0
EC No.	200-896-5
Appearance	Specialty Gas
Packaging	DOT cylinder
HS Code	29033928
UN No.	1982
Hazardclass	2.2

**Applications:**

Carbon tetrafluoride is currently the most widely used plasma etching gas in the microelectronics industry. It is widely used for etching thin film materials such as silicon, silicon dioxide, silicon nitride, phosphorus silicon glass, and tungsten. It is used for surface cleaning of electronic devices, production of solar cells, laser technology, low-temperature refrigeration, gas insulation, leak detection agents, controlling spacecraft attitude, and as a detergent in printed circuit production. Lubricants and brake fluids are also widely used. Due to its strong chemical stability, CF<sub>4</sub> can also be used in metal smelting and plastic industry.